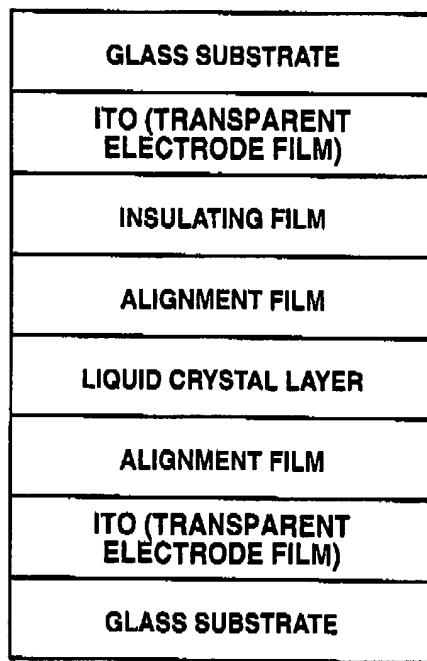
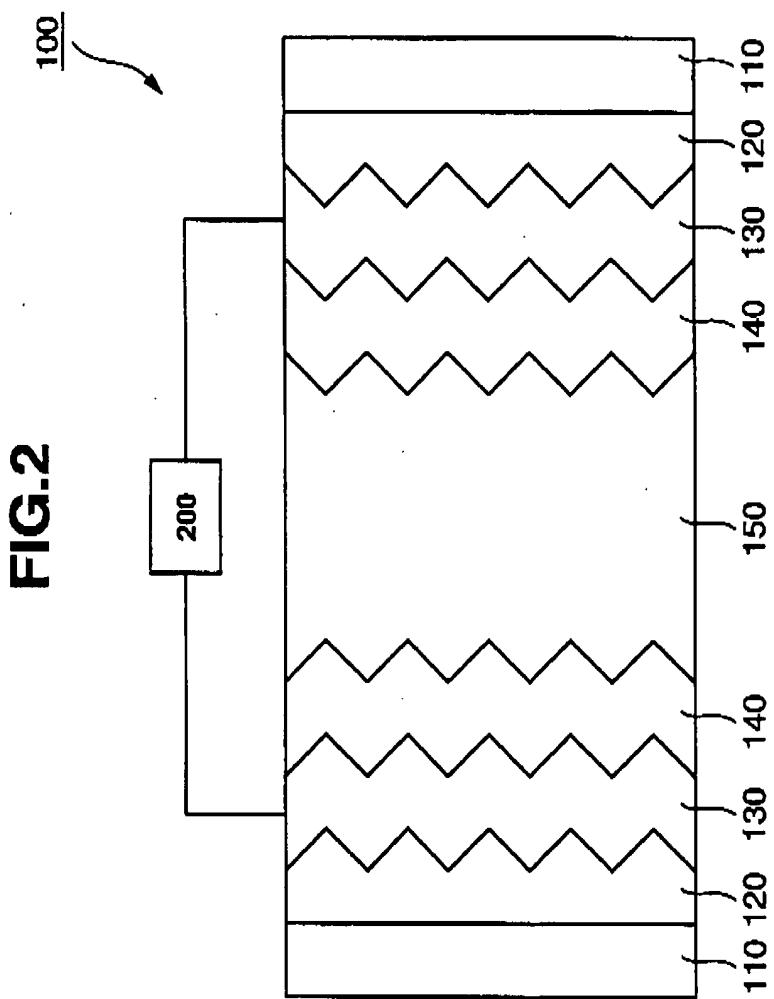


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FIG.1**(PRIOR ART)**

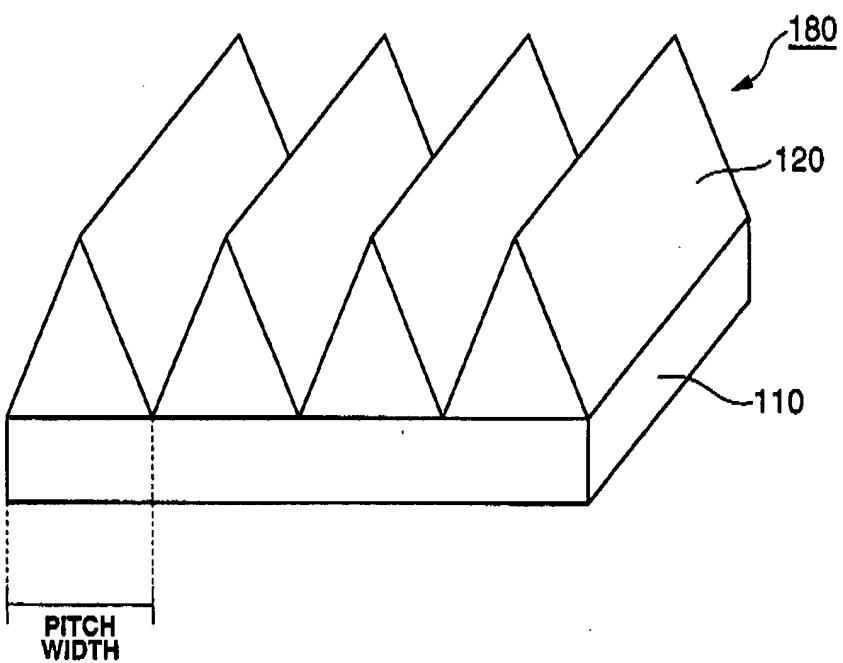
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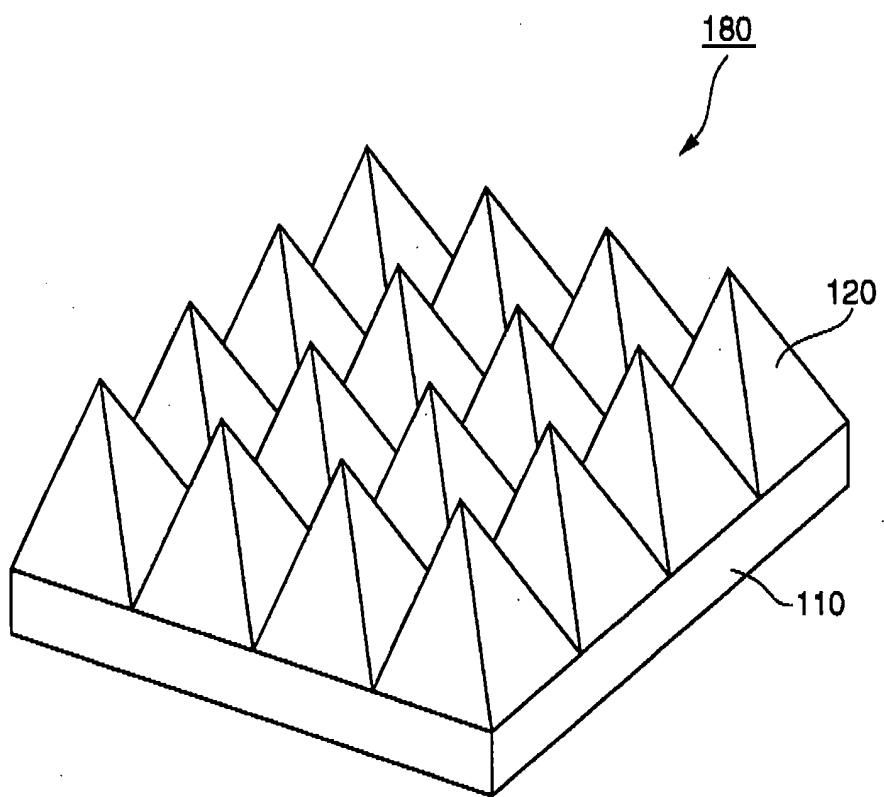
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FIG.3



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FIG.4



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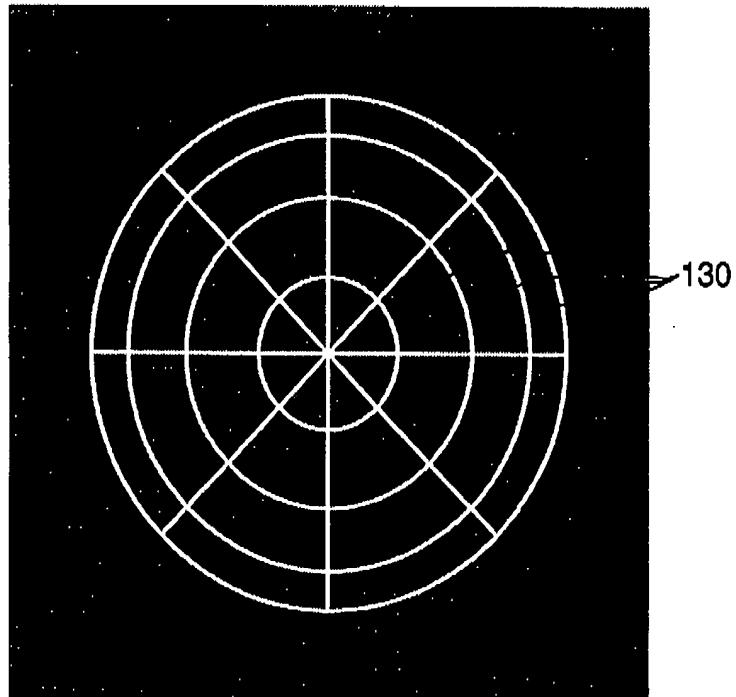
NO. 0784

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FIG.5



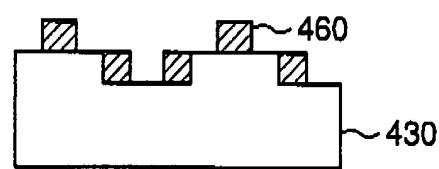
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FIG.6**(a)****(d)**

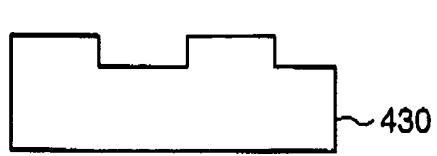
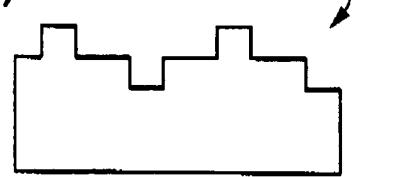
↓
EXPOSURE·
DEVELOPMENT

↓
EXPOSURE·
DEVELOPMENT

(b)**(e)**

↓
ION BEAM
ETCHING

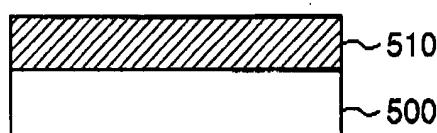
↓
ION BEAM
ETCHING

(c)**(f)**

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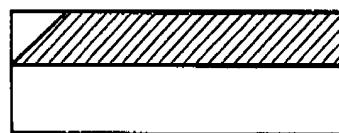
FIG.7

(a)

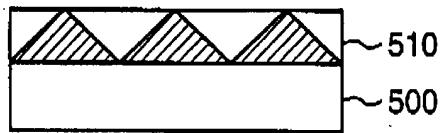


(b)

↓
CONTROLLED DOSE
AMOUNT OF
ELECTRON BEAM



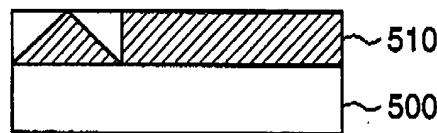
(e)



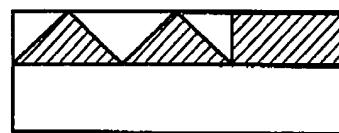
(f)



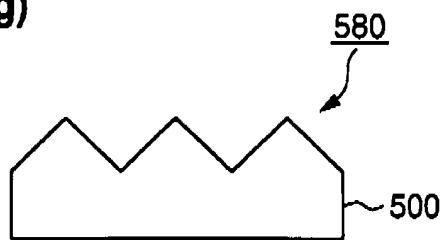
(c)

↓
DEVELOPMENT

(d)

↓
ETCHING

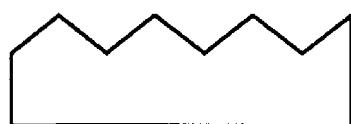
(g)



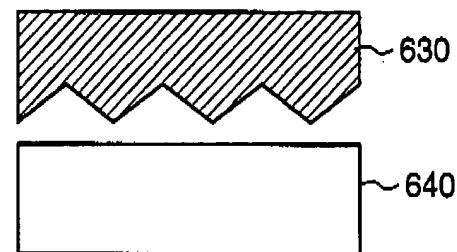
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FIG.8

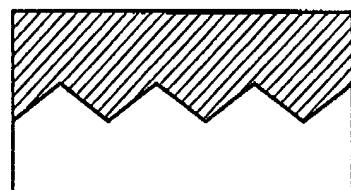
(a)



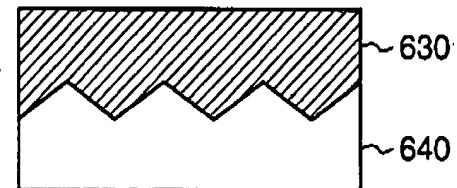
(d)



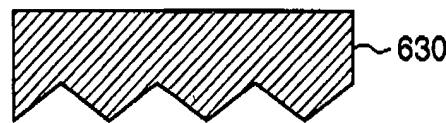
(b)



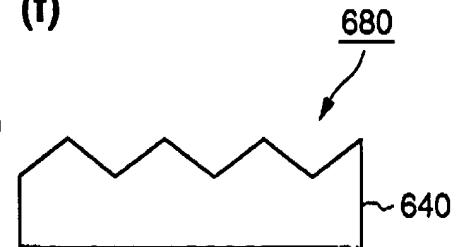
(e)



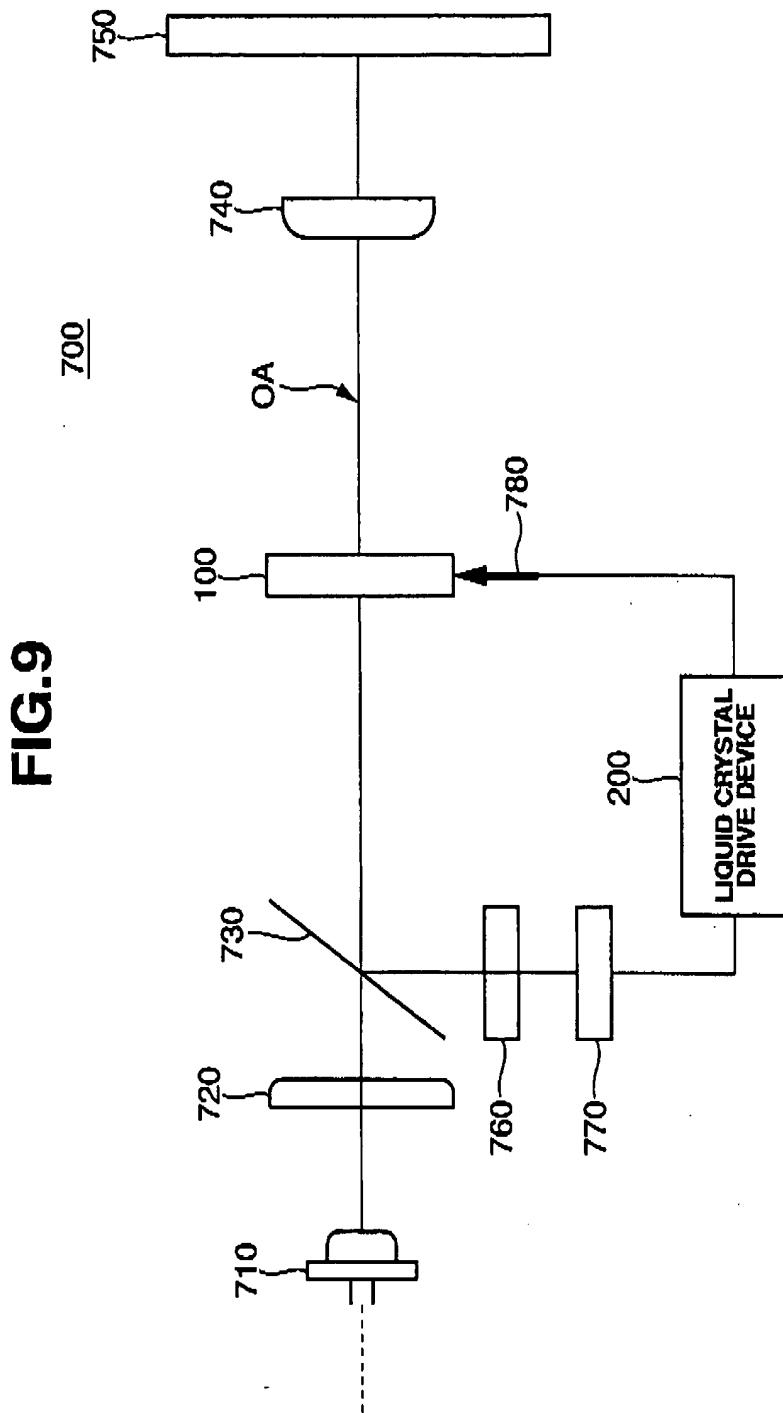
(c)



(f)

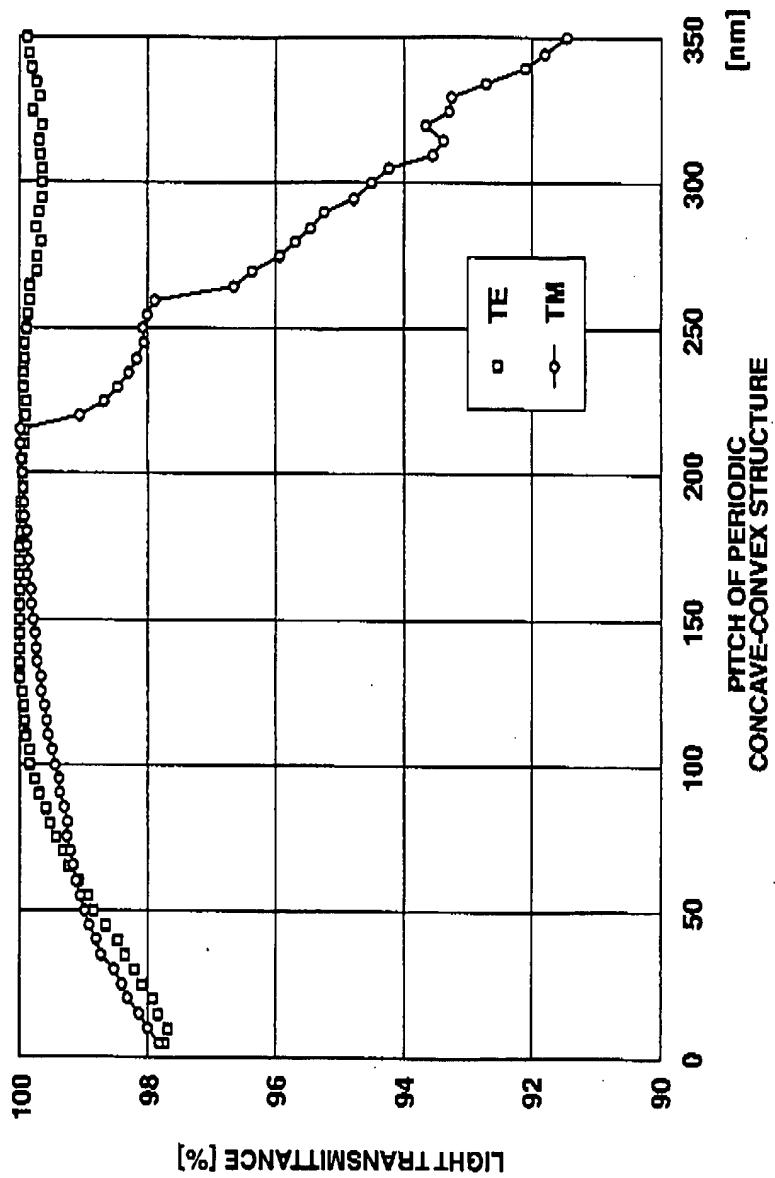


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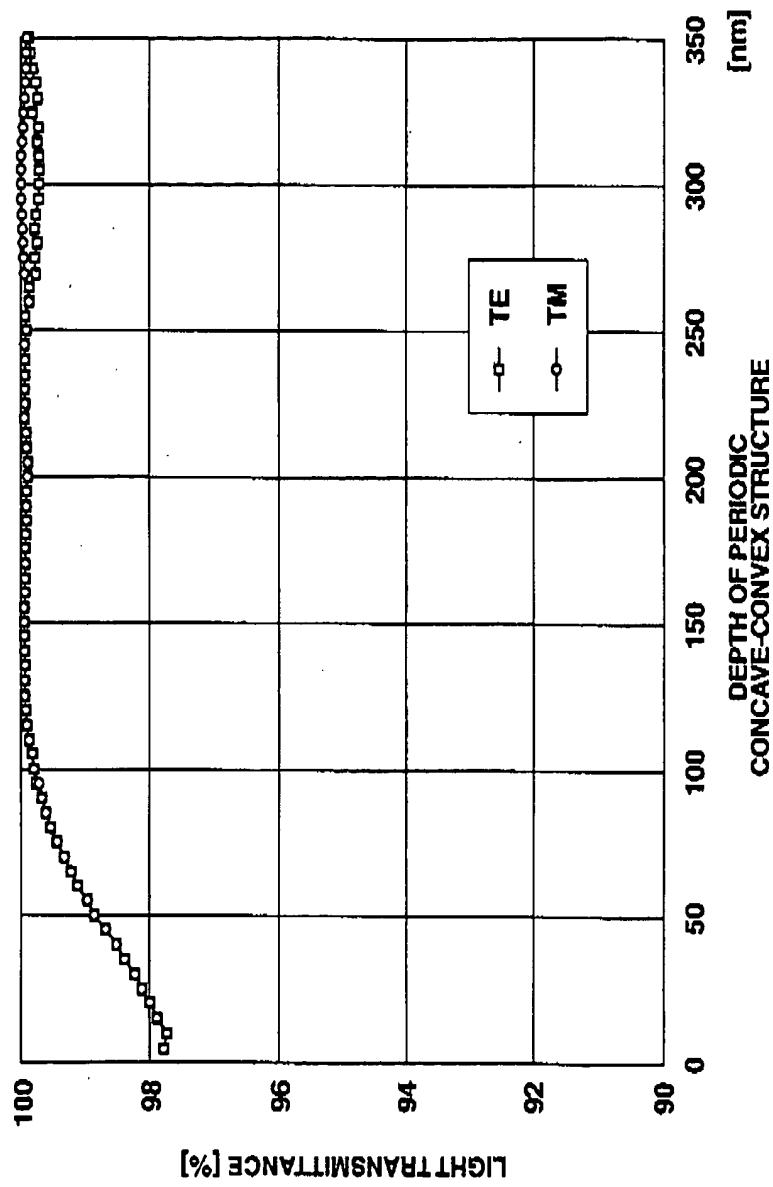
FIG.10



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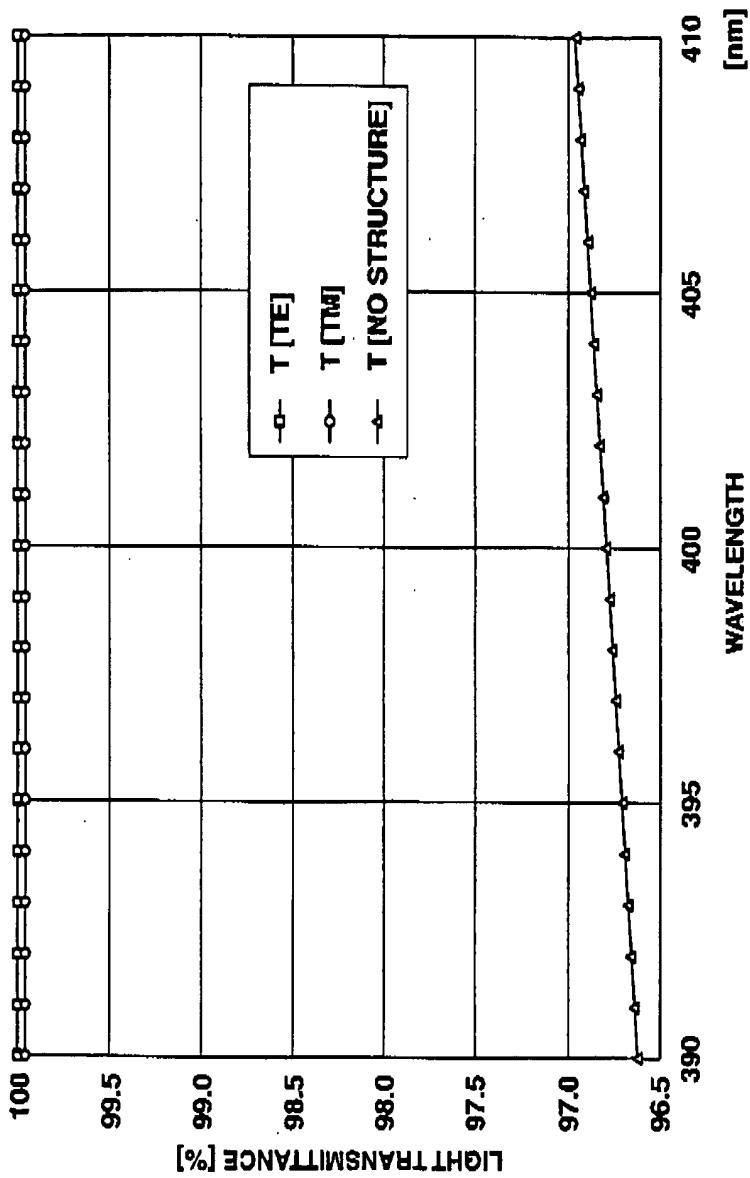
FIG.11



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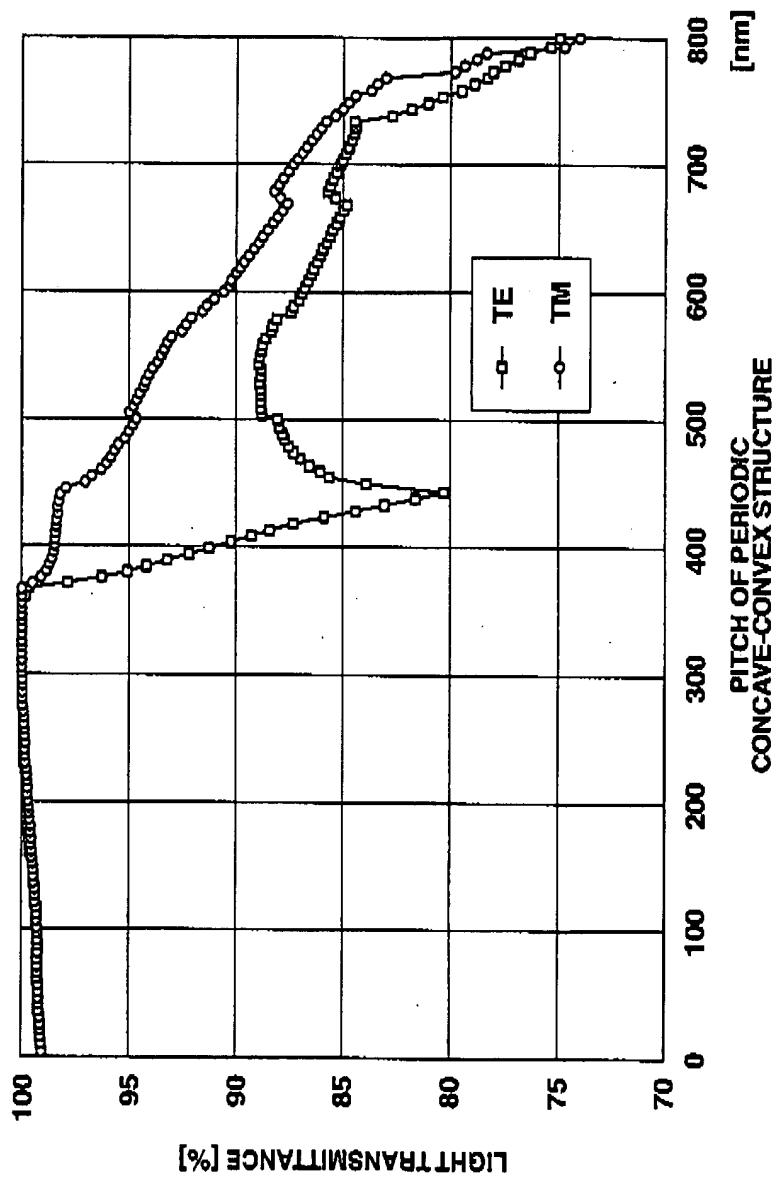
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FIG.12



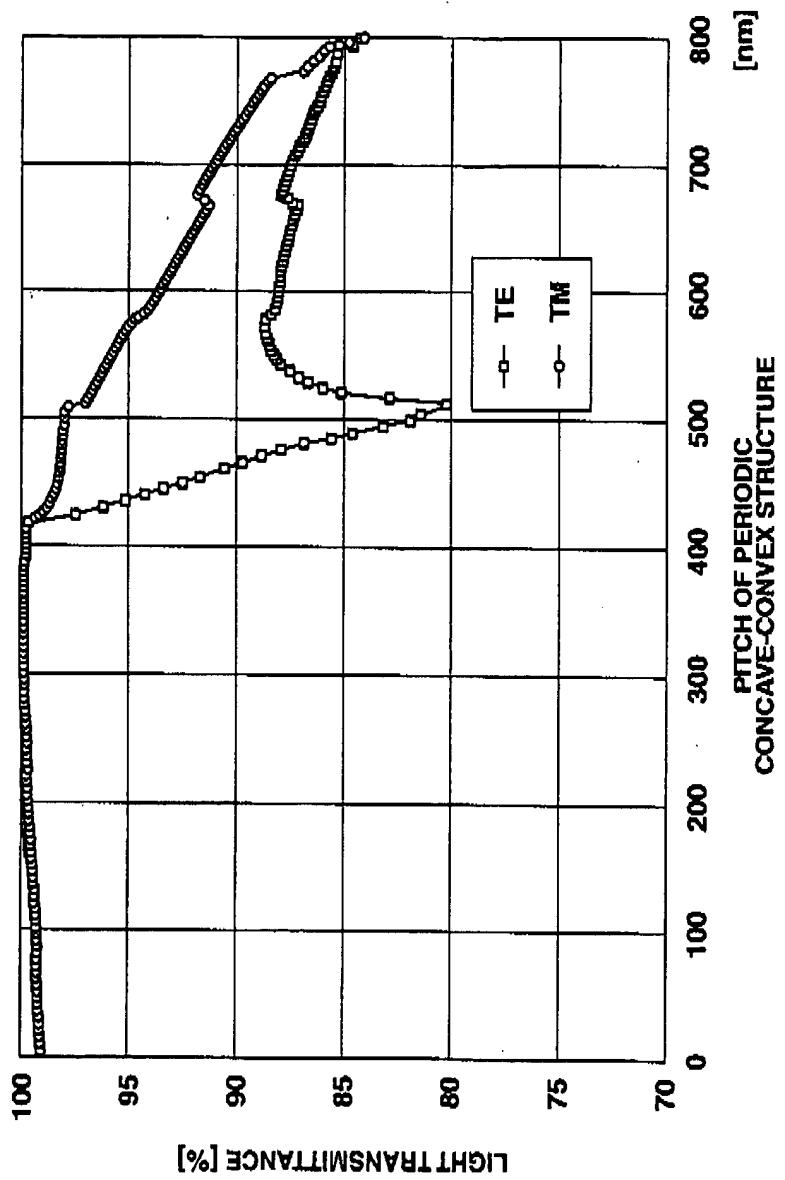
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FIG.13



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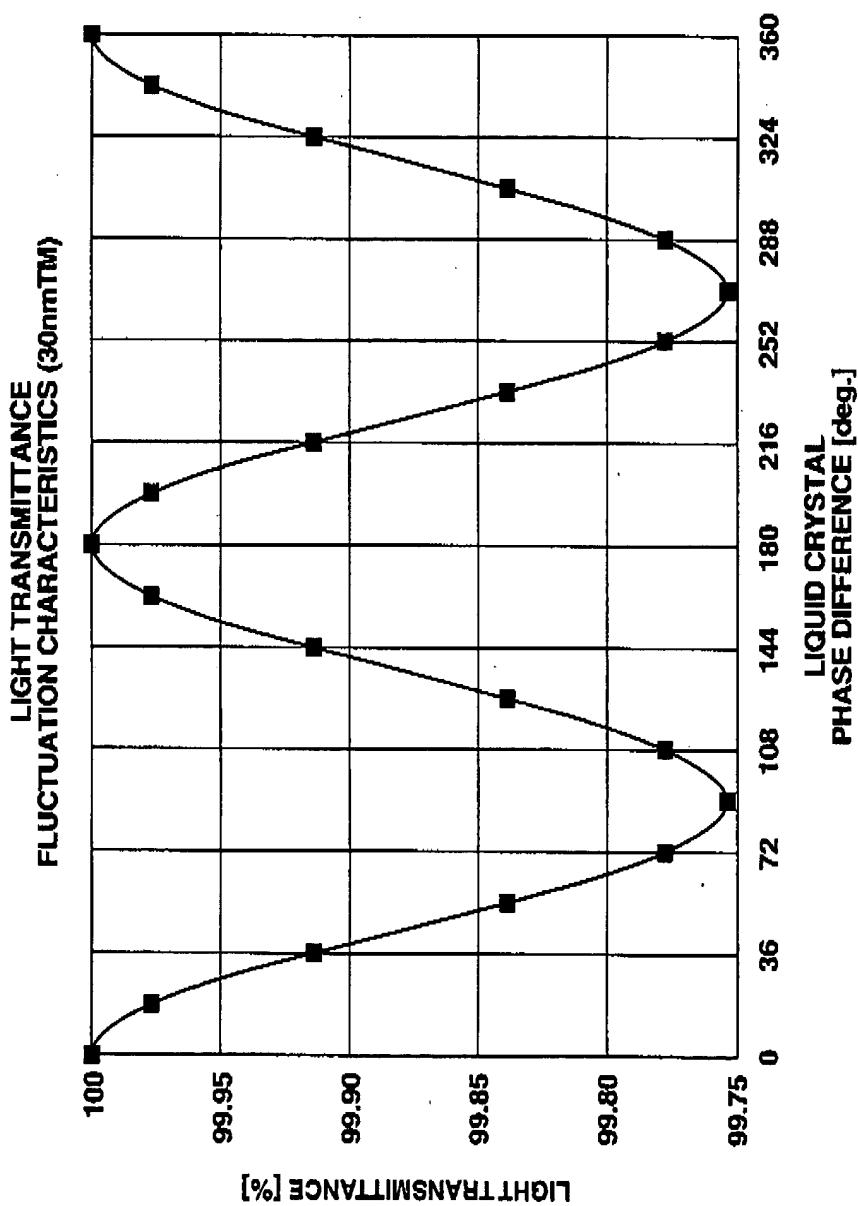
FIG.14



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FIG. 15



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FIG.16

